

**REMARKS**

Claims 1-11 and 13-31 are now present in the application. Claims 1, 22, 30 and 31 are independent claims. Claims 1, 22, 30 and 31 have been amended. Reconsideration of this application, as amended, is respectfully requested.

**Rejections Under 35 U.S.C. § 103**

Claims 1, 2, 5-9, 11,13, 15, 16, 20-22, 24 and 28-31 stand rejected under 35 U.S.C. §103(a) over U.S. Patent No. 5,771,110 to Hirano et. al. (Hirano) in view of U.S. Patent No. 6,133,145 to Chen, and claims 10, 17-19 and 25-27 stand rejected over Hirano and Chen as applied to claims 1, 7, 22 and 30 in view of U.S. Patent No. 5,968,847 to Ye et al. (Ye), and claims 3, 4, 14 and 23 stand rejected over Hirano and Chen and further in view of Muraguchi. These rejections are respectfully traversed.

Independent claim 1 has been amended to recite a combination of steps in a method of manufacturing a liquid crystal display device, including wherein said depositing a metal layer on the passivation layer, forming a photoresist pattern, treating the exposed portion of said metal layer and etching the treated portion of said metal layer are sequentially performed, said etching the treated portion of said metal layer being the first step of etching performed in said sequence.

Independent claim 22 has been amended to recite a combination of steps in a method of patterning a metal layer, including said depositing a metal layer over a substrate, forming a mask on a surface of the metal layer, exposing the uncovered portion of said metal layer and etching the uncovered portion of said metal layer are sequentially performed, said etching the uncovered portion of said metal layer being the first step of etching performed in said sequence.

Independent claim 30 has been amended to recite a combination of steps in a method of manufacturing a pixel electrode in a liquid crystal display device, including said depositing a metal layer on the passivation layer, forming a photoresist pattern, exposing the uncovered portion of said metal layer and etching the uncovered portion of said metal layer are sequentially performed, said etching the uncovered portion of said metal layer being the first step of etching performed in said sequence.

Independent claim 31 has been amended to recite a combination of steps in a method of manufacturing a pixel electrode in a liquid crystal display device, including said depositing a metal layer on the passivation layer, forming a photoresist pattern, exposing the uncovered portion of said metal layer and etching the uncovered portion of said metal layer are sequentially performed, said etching the uncovered portion of said metal layer being the first step of etching performed in said sequence.

Applicant respectfully submits that these combinations of steps as recited in independent claims 1, 22, 30 and 31 are not disclosed or fairly suggested by the prior art of record, including Hirano and Chen.

**Hirano in View of Chen**

The Office Action admits that certain deficiencies are present in Hirano, and relies on Chen to supply the deficiencies. In the Response to Arguments, the Office Action asserts that sequentially claiming steps does not rule out the presence of intermediate steps. Particularly, the Office Action states that “the sequence of Chen merely has an extra etching step”. The Applicant does not entirely disagree that Chen has an extra etching step.

However (as the Examiner will note), claims 1, 22, 30 and 31 (as amended) rule out the presence of the extra etching step of Chen. Particularly, the Applicant’s claimed etching step is the first etching step in the sequence. In Chen (as the Examiner has noted), an etching step is performed prior to the Applicant’s claimed etching step. Therefore, since the Applicant’s claimed sequence is different from the sequence of Chen, the combination of Hirano and Chen cannot render obvious any combination recited in the pending claims.

For the reasons explained above, Applicant therefore respectfully submits that the combinations of elements as set forth in independent claims 1, 22, 30

and 31 are not disclosed or made obvious by the prior art of record, including Hirano and Chen. Accordingly, reconsideration and withdrawal of this rejection are respectfully requested.

Claims 2, 5-9, 11, 13, 15, 16, 20, 21, 24, 28 and 29 depend, either directly or indirectly, on claims 1, 22 and 30. Since neither Hirano, nor Chen, discloses or suggest the features of independent claims 1, 22, 30 and 31, Hirano, in view of Chen, cannot render claims 1, 2, 5-9, 11, 13, 15, 16, 20-22, 24 and 28-31 obvious to one of ordinary skill in the art.

Claims 3, 4, 10, 14, 17-19, 23 and 25-27, also depend on claims 1, 22, and 30. Since neither Hirano, nor Chen, nor Ye, nor Muraguchi discloses or suggests the features of independent claims 1, 22, and 30, Hirano and Chen, in view of Ye, or Hirano and Chen in view of Muraguchi cannot render claims 3, 4, 10, 14, 17-19, 23 and 25-27 obvious to one of ordinary skill in the art.

Reconsideration and withdrawal of these art grounds of rejection are respectfully requested.

### **Conclusion**

Applicant considers all of the Examiner's comments to have been addressed and all of the Examiner's rejections overcome, thereby placing all claims pending in the present Application in condition for allowance. Accordingly, a Notice of Allowability is solicited in earnest.

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Response to Office Action of February 3, 2005

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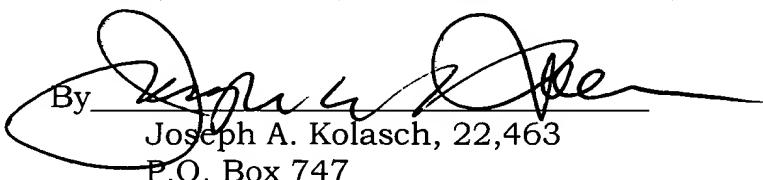
Pursuant to 37 C.F.R. §§ 1.17 and 1.136(a), Applicant(s) respectfully petition(s) for a two (2) month extension of time for filing a reply in connection with the present application, and the required fee of \$450.00 is attached hereto.

Should there be any outstanding matters that need to be resolved in the present application, the Examiner is respectfully requested to contact Robert E. Goozner, Ph.D. (Reg. No. 42,593) at the telephone number of the undersigned below, to conduct an interview in an effort to expedite prosecution in connection with the present application.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. §§ 1.16 or 1.17; particularly, extension of time fees.

Respectfully submitted,

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